

The Laurell 650 Advantage

Choosing your best spin processor

All Laurell Technologies 650 series spin processors come with the following benefits

650 Digital Process Controller — easy to program without a manual with many advanced capabilities

Time: 1 second to 99 minutes 59.9 seconds in 0.1 second increments

Programs: twenty 51-step programs or manual mode — number of steps/programs can be user reconfigured through SPIN 3000

SPIN 3000 field-proven advanced PC interface software included, not required to program system

Class 1 Bluetooth® (100 meter / 328 ft range) — offered as standard (no cable or converter)

Fluid-control lid directs materials towards rear drain — no drips encountered when opening chamber

Clear View lid Chemically resistant with Ø3/4" (Ø19 mm) center opening

Ø1.5" (Ø38 mm) NPP Drain Port and Nitrogen purge

Safety door interlock (disallows rotation when door is open)

Safety door latch (requires deliberate action to open process chamber)

Safety door lock (prevents chamber opening while program is running, or during chuck rotation after program ends)

Vacuum interlock (disallows rotation when there is insufficient vacuum)

Corrosion-proof configuration (no exposed metal — therefore, no degradation using strong acids or bases)

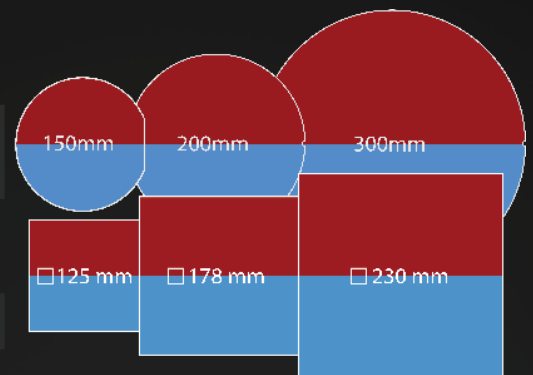
Glovebox-ready configuration (Continuous seal purge with CDA or inert gas required)

Lifetime Process Support

Choose a size that fits your substrate

	23 Series	8 Series	15 Series
Round substrates up to:	150 mm/ 6 inches	200 mm/ 8 inches	300 mm/ 12 inches
Square substrates up to:	125mm/ 5 inches	178 mm/ 7 inches	230 mm/ 9 inches

The indicated measurements for square substrates are the length of a side



WS-650Mz-23NPP



WS-650Hz-8NPP



WS-650Hz-15NPP

Required facilities



95 - 250v AC at 47-63 Hz



60-70 psig (4-5 bar) of N² or
Clean Dry Air



20-28 inches (~504-711mm) Hg.
1.7 - 4.5 SCFM (0.127 M³/min.)

Choose the housing material based on your process and chemistry:

Polypropylene Copolymer

- An exclusive copolymer resistant to solvents, strong acids, and bases

Teflon®

- Widest chemical resistance available
- Required for processing aggressive chemistries such as "Piranha" etch and certain acids at high concentrations

Choose the motor performance that suits your process, now and in the future:

Lz Improved Performance Motor

- Brushless motor suitable for N₂ or Ar environments
- Speed range from 1 to 12,000 RPM
- Acceleration up to 12,000 rpm/second*
- Bi-directional rotation
- Optional homing feature
- Limited lifetime warranty

**Substrate size / weight dependent*

Hz High Performance Motor

- Brushless motor
- Speed range from 1 to 12,000 RPM
- Acceleration up to 12,000 rpm/second*
- No measurable speed error
- Powerful: Spin larger, heavier substrates
- Forward/Reverse rotation
- Programmable Agitation
- Limited lifetime warranty

Choose the accessories that will help you achieve your best results:

Dispense Solutions

- **UD-3** center dispense
- **UD-3b** off center dispense and Edge Bead Removal
- **Single Shot Dispense** from an open container
- **Single syringe** manual dispense
- **Multi-syringe** manual dispense

Chucks: Standard and Custom

- **Non-vacuum** chucks
- **Minimum contact** chucks
- **Fragment** chucks
- **Basket processing** chucks
- **CD/DVD** chucks
- **High-Porosity** chucks
- **Lens** chucks
- **Embedded** chucks

Wireless Control

- **Remote vacuum** switch
- **Footswitch**
- **Multi-System** control

Choose the experts:

Since 1985 **Laurell Technologies** has created a broad range of unique solutions for our customers.

Laurell EDC systems for aqueous processing are custom designed to fit your specific chemistry, process requirements, and ensure your safety

Discuss your needs with our experienced engineers for a complete solution.



Intertek

All Laurell products that carry the ETL mark meet, or exceed, specific US and Canadian product safety standards



Telephone: 215-699-7278
Fax: 215-699-4311
Email: sales@laurell.com

Laurell Technologies inc.
1400 Pennbrook Pkwy
Lansdale, 19446 USA